2/27/4

IN THE UNITED STATES PAT

Docket No.: 20046/0200815-US0

(PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Franz Hofmann et al.

Application No.: 10/768,971

application 110.: 10//00,5/1

Filed: January 30, 2004

For: A FIN FIELD-EFFECT TRANSISTOR AND

METHOD FOR PRODUCING A FIN FIELD-

**EFFECT TRANSISTOR** 

Confirmation No.:

Art Unit: N/A

Examiner: Not Yet Assigned

## **INFORMATION DISCLOSURE STATEMENT (IDS)**

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Pursuant to 37 CFR 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached PTO/SB/08. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is filed within three months of the U.S. filing date (37 CFR 1.97(b)(1)).

A copy of each document on the PTO/SB/08 is attached. Pursuant to the Notice issued by the United States Patent and Trademark Office dated July 11, 2003 waiving the requirements of 37 C.F.R. 1.98(a)(2)(i), copies of the United States Patents on PTO/SB/08a are not submitted.

Application No.: 10/768,971 2 Docket No.: 20046/0200815-US0

In accordance with 37 CFR 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 CFR 1.56(a) exists. In accordance with 37 CFR 1.97(h), the filing of this Information Disclosure statement shall not be construed to be an admission that any patent, publication or other information referred to therein is "prior art" for this invention unless specifically designated as such.

It is submitted that the Information Disclosure Statement is in compliance with 37 CFR 1.98 and the Examiner is respectfully requested to consider the listed documents.

The Commissioner is authorized to charge any deficiency of up to \$300.00 or credit any excess in this fee to Deposit Account No. 04-0100.

Dated: February 25, 2004

Respectfully submitted,

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application No. (if known): 10/768,971

Attorney Docket No.: 20046/0200815-US0

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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

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Complete if Known				
Application Number	10/768,971			
Filing Date	January 30, 2004			
First Named Inventor	Franz Hofmann			
Art Unit	N/A			
Examiner Name	Not Yet Assigned			
Attorney Docket Number	20046/0200815-US0			

	U.S. PATENT DOCUMENTS						
Examiner Cite Initials* No.	Cita	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where		
	No.1	Number-Kind Code <sup>2</sup> ( if known)			Relevant Passages or Relevant Figures Appear		
	AA	US-4,996,574-B1	02-26-1991	Shirasaki			
	AB	US-5,300,455-B1	04-05-1994	Vuillermoz et al.			
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Examiner Initials*	Cite No.1	Foreign Patent Document  Country Code <sup>3</sup> -Number <sup>4</sup> -Kind Code <sup>4</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>

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		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
	CA	Fujiwara, A. et al: "Suppression of Unintentional Formation of Parasistic SI Islands on ASI Single-Electron Transistor by the Use of Sin Masked Oxidation"; Extended Abstracts of the 1997 International Conference on Solid State Devices and Materials, Japan Society of Applied Physics. Tokyo, Japan, 1 September 1997, pages 482-483.	
	СВ	Ishii, T. et al: "Characterization of One-Dimensional Conduction in an Ultra-Thin Poly-Si Wire"; Extended Abstracts of the International Conference on Solid State Devices and Materials", Japan Society of Applied Physics. Tokyo, Japan, 21 August 1995, pages 201-203.	
	CC	Hisamoto, Digh et al: "A Fully Depleted Lean-Channel Transistor (DELTA) - A Novel Vertical Ultrathin SOI MOSFET"; IEEE Electron Device Letters, Vol. 11, No. 1, January 1990, pages 36-38.	
	CD	Hisamoto, Digh et al: "A Folded-Channel MOSFET for Deep-sub-tenth Micron Era"; IEDM 98, pages 1032-1034, 1998.	
	CE	Kedzierski, Jakub et al: "Complementary silicide source/drain thin-body MOSFETS for the 20nm gate length regime"; IEDM 2000, pages 57-60.	

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